

Notice of References CitedApplication/Control No.
10/050,743Applicant(s)/Patent Under
Reexamination
SCHEUER ET AL.Examiner
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2881

Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,883,017	03-1999	Tepman et al.	438/800
	B	US-6,528,804	03-2003	Sullivan et al.	250/492.21
	C	US-			
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	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Chu et al., " Apparatus and Method for Direct Current Plasma Immersion Ion Implantation ", Pub. No. US 2001/0046566 A1, □□publication date: November 29, 2001.
	V	
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.